





Applicant(s): Hsiao, Tommy C.; Hui, Angela T.; Ogle, Robert B.; Pham, Tuan Duc;

Plat, Marina V.; Ramsbey, Mark T.; Shen, Lewis

Assignee: Advanced Micro Devices, Inc.

Title: Polished Flash Process With Metal Gates And Improved Planarity

Serial No.: 09/430,366

Filing Date: 10/28/99

Examiner:

J. Chen

Group Art Unit: 2813

Docket No.:

M-7523 US

San Jose, California May 12, 2000

BOX

ASSISTANT COMMISSIONER FOR PATENTS

Washington, D. C. 20231

## RESPONSE TO RESTRICTION REQUIREMENT

Dear Sir:

In response to the Restriction Requirement of April 12, 2000, Applicants hereby elect without traverse Group I (i.e., Claims 1-15) for further prosecution in the above-referenced patent application. Applicants reserve the right to file one or more divisional patent application upon the unelected claims (i.e., Claims 16-20). If the Examiner has any questions regarding the above, the Examiner is requested to telephone the undersigned Attorney for Applicants at 408-453-9200.

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 2023), on \_\_\_\_\_\_\_\_, 2000.

Attorney for Applicant(s)

Date of Signature

Respectfully submitted,

1987 I

Edward C. Kwok

Attorney for Applicant(s)

Reg. No. 33,938

LAW OFFICES OF SKJERVEN, MORRILL, MACPHERSON, FRANKLIN & FRIEL LLP

> 25 METRO DRIVE SUITE 700 SAN JOSE, CA 95110 (408) 453-9200 FAX (408) 453-7979

> > Serial No. 09/430,366

-1-